

Yielding and plastic slip in ZnO

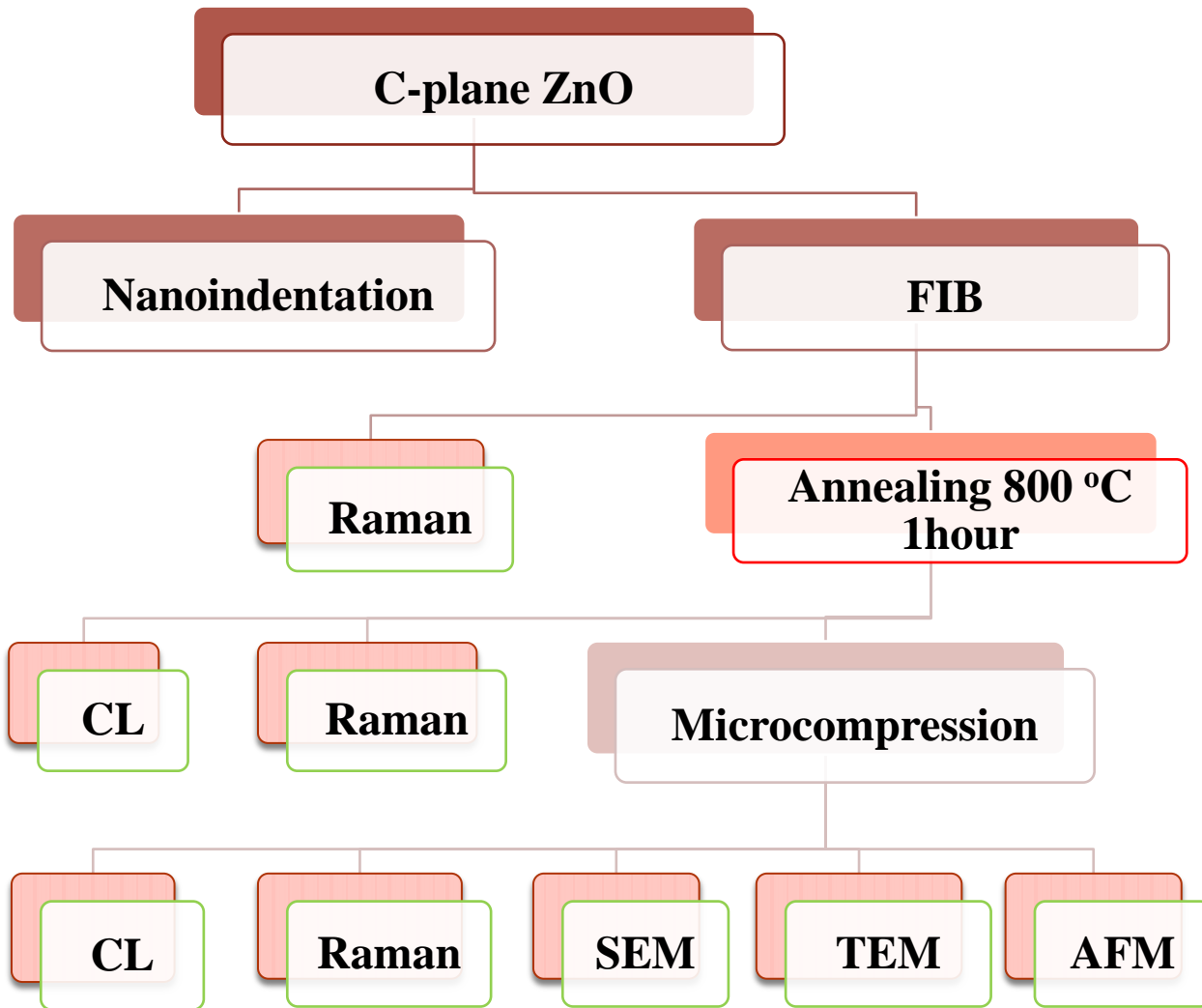
Adviser: Prof. Huang, Prof. Nieh

Student: Welson T.H. Sung

Mar. 7th, 2012

Outline

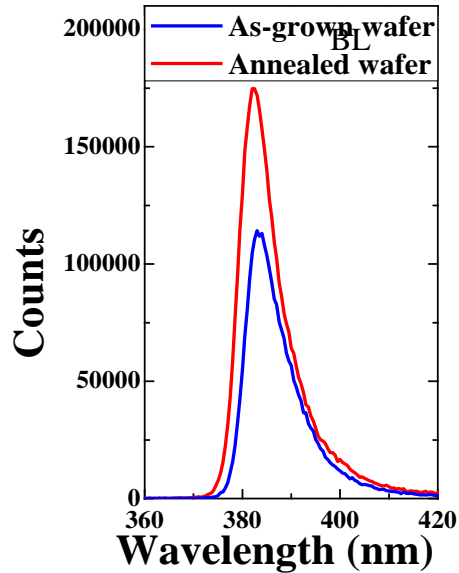
- Residual stress and defect density
- Nanoindentation testing
- Microcompression



The mechanical properties of ZnO

	Structure	Method	E (GPa)	H (GPa)	Slip system	Reference	
Polycrystalline	Bulk	Calculation	120	-	-	Shein et al. 5	
		Experiment	140	-	-	Shein et al. 5	
Single crystalline	Bulk	Nanoindentation	123 *	5.1	-	Present work	
			111	5	Pyramidal	Bradby et al. 4	
			112	5.4	Pyramidal	Jain et al. 15	
	Micropillar	Microcompression	118	-	Pyramidal	Present work	
	Nanorod	Nanoindentation	63	9.7	-	Yan et al. 9	
	Nanowire	Tension		21	-	-	Desai et al. 20
				160	-	-	Xu et al. 21
Nanobelt	Bending		31.1	2.5	-	Ni et al. 8	
	Bending		51	-	-	Bai et al. 22	

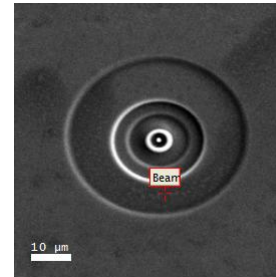
CL – annealed effect



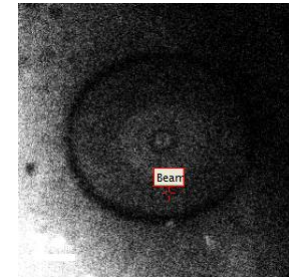
Blue luminescence				
		ISU	A800	
Wavelength	P1	383.1	381.9	
FWHM		4.5	4.8	
Wavelength	P2	388.0	386.6	
FWHM		8.1	8.0	
Intensity		114538	174653	1.5 times

Wave length = 383 nm

Unannealed

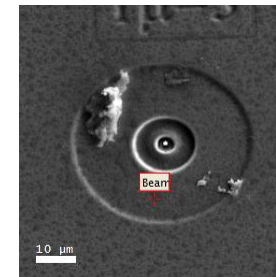


SEM image

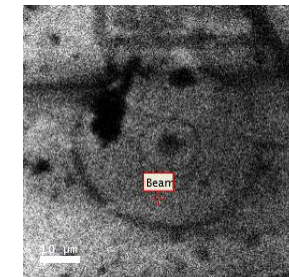


CL image

Annealed 800 °C

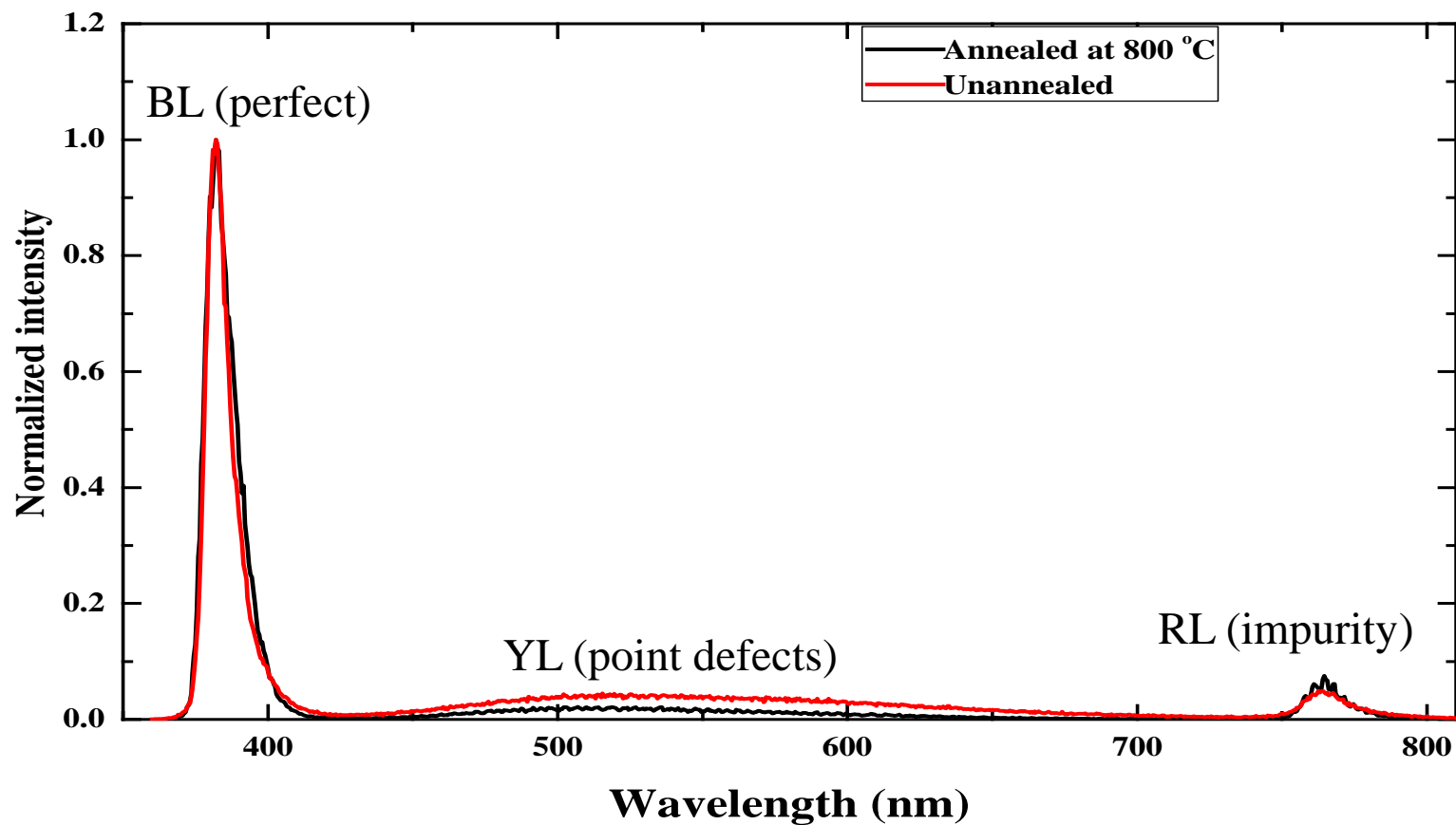


SEM image

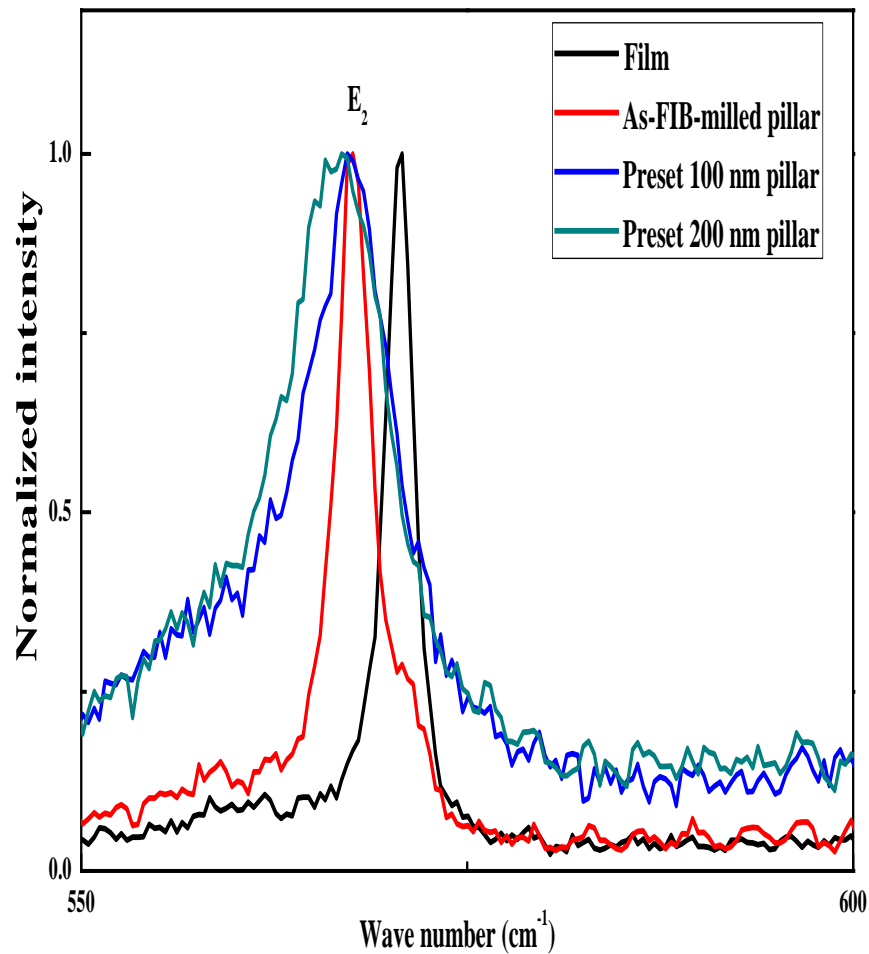


CL image

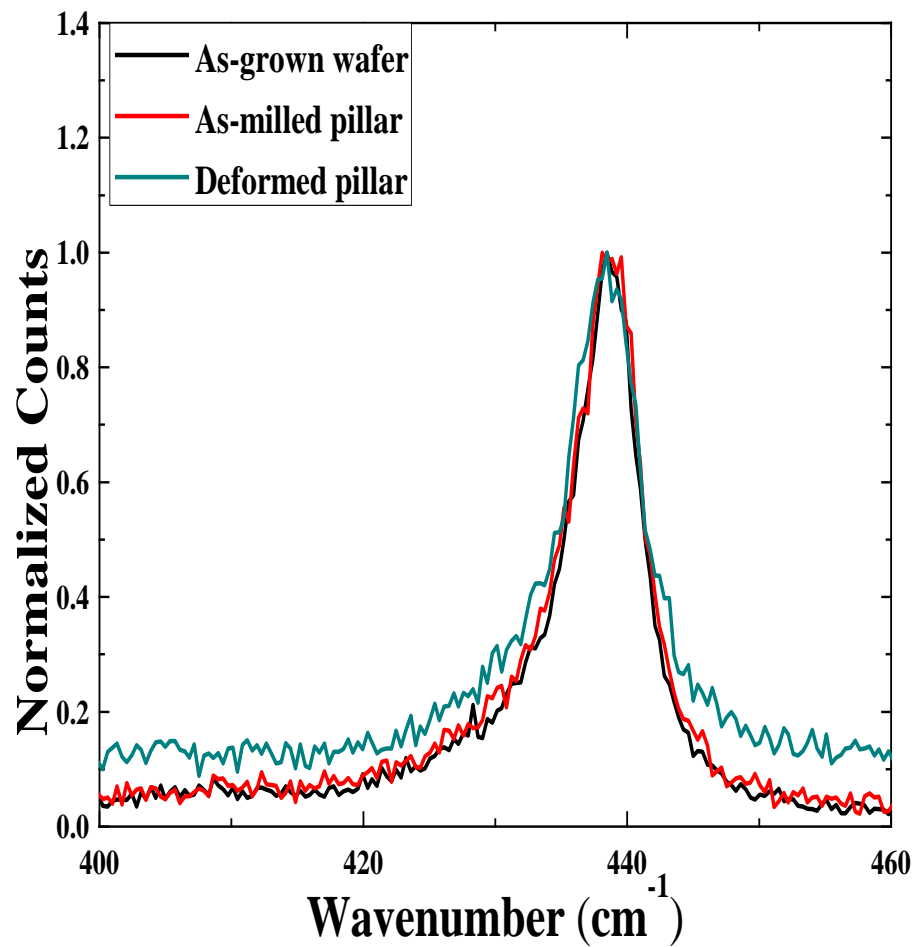
CL Spectrum



Raman – residual stress



GaN/Sapphire thin film

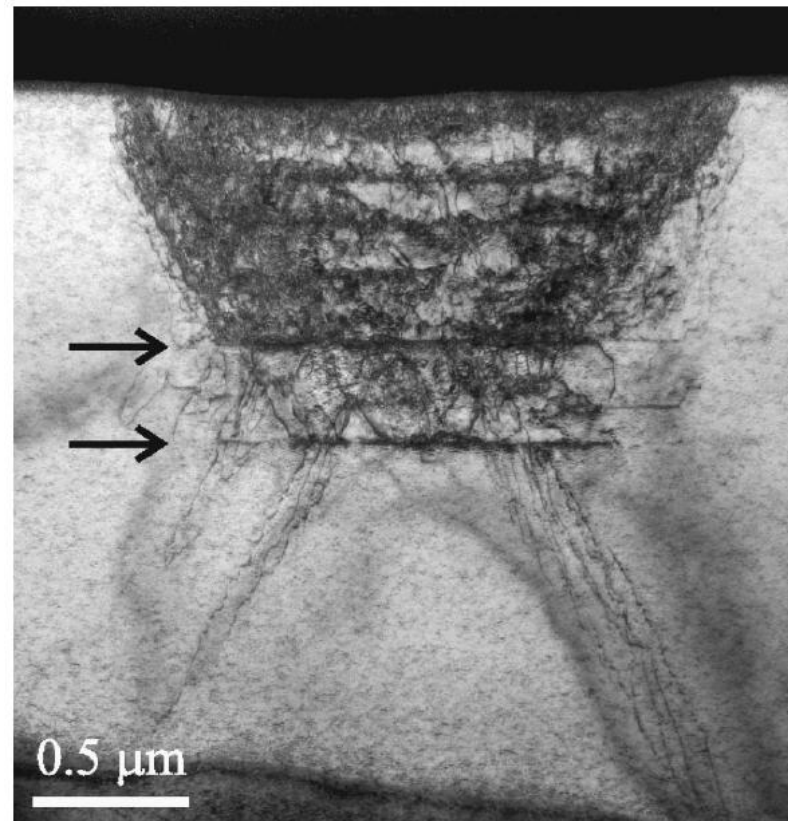
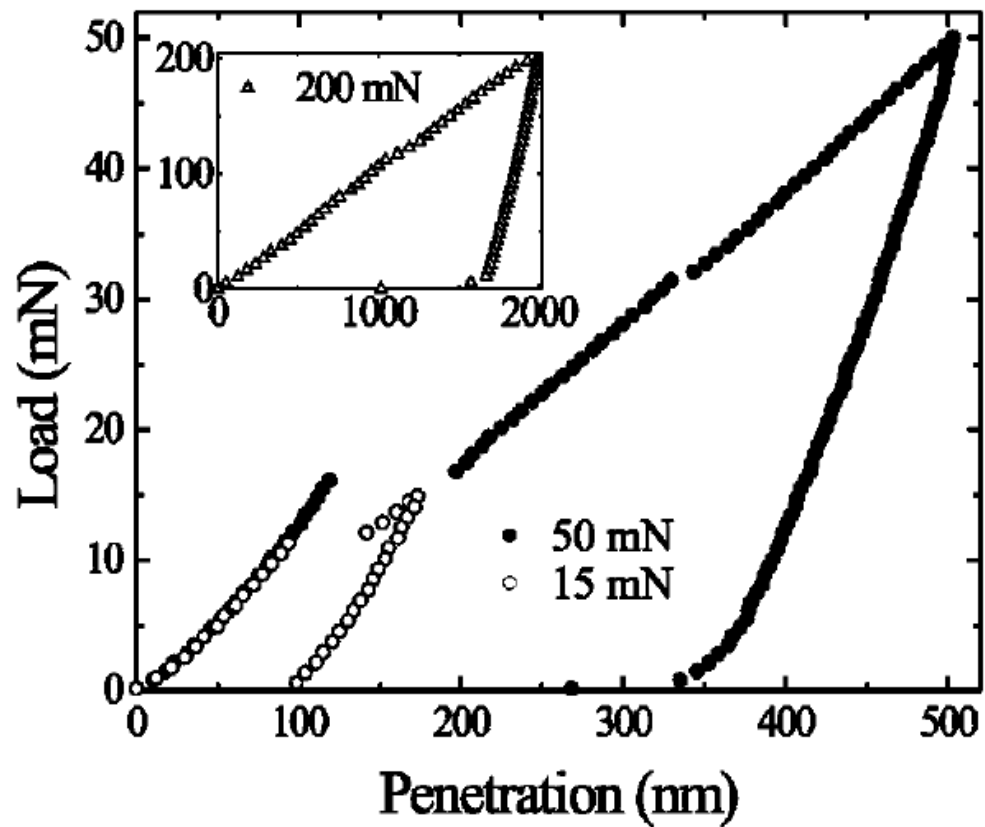


ZnO wafer

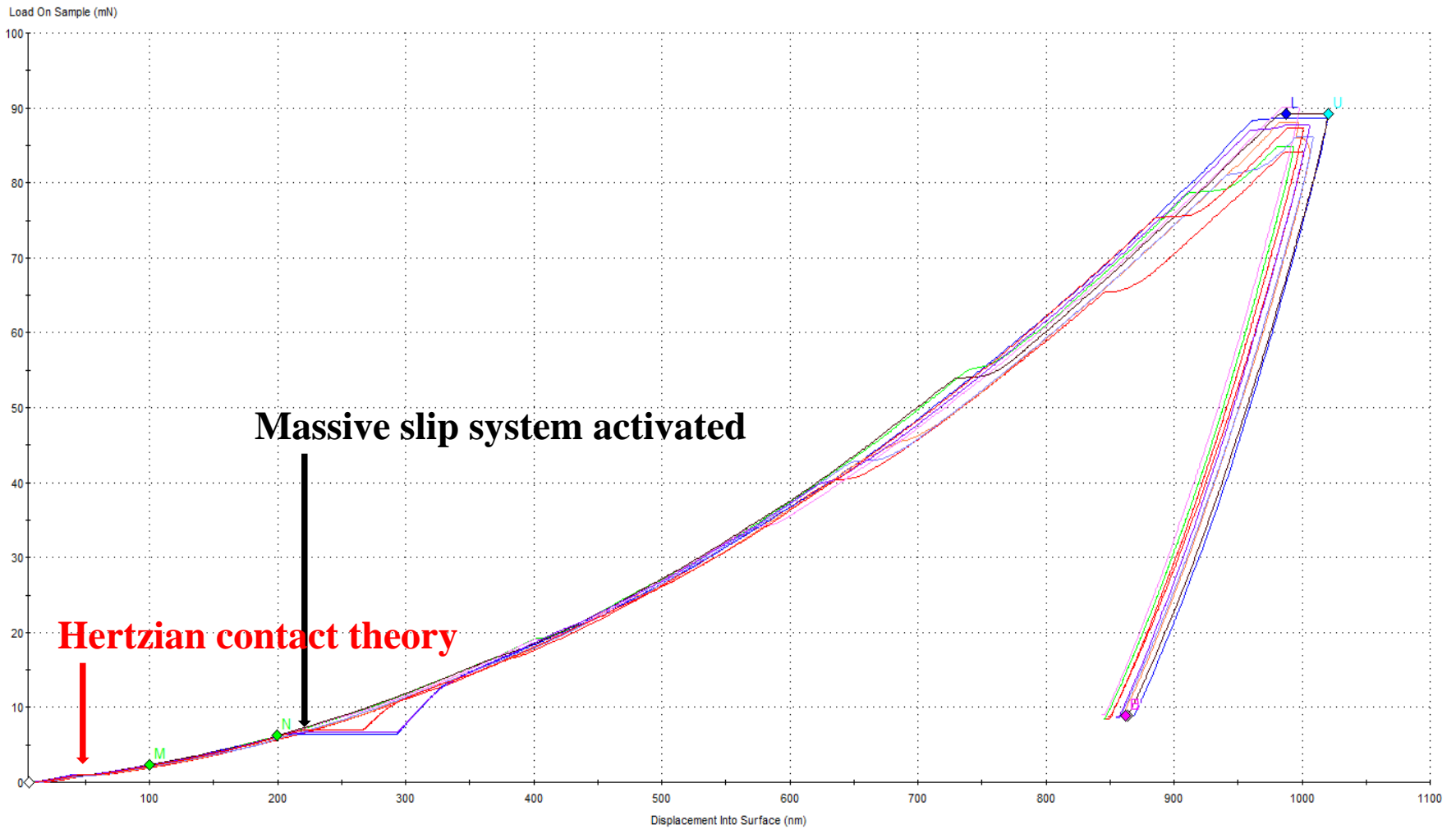
Conclusion

- No residual stress remains in wafer, as-grown pillar and deformed pillar.
- The improved BL intensity in CL spectrum in the annealed wafer was apparently due to the reduction of defect density not residual stress.

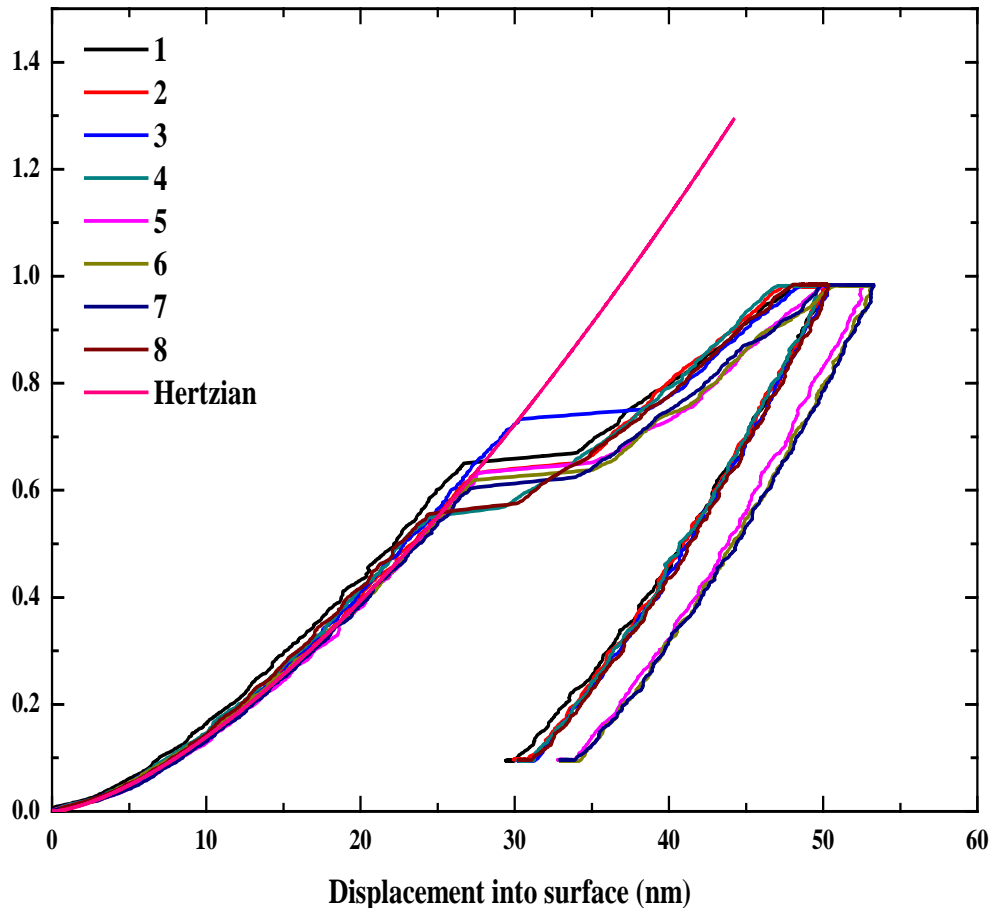
Nanoindentation



Nanoindentation



Nanoindentation of as-grown ZnO



Hertzian contact theory

- For shallow displacement < 100 nm

$$P = \frac{4}{3} E_r \sqrt{R \delta}$$

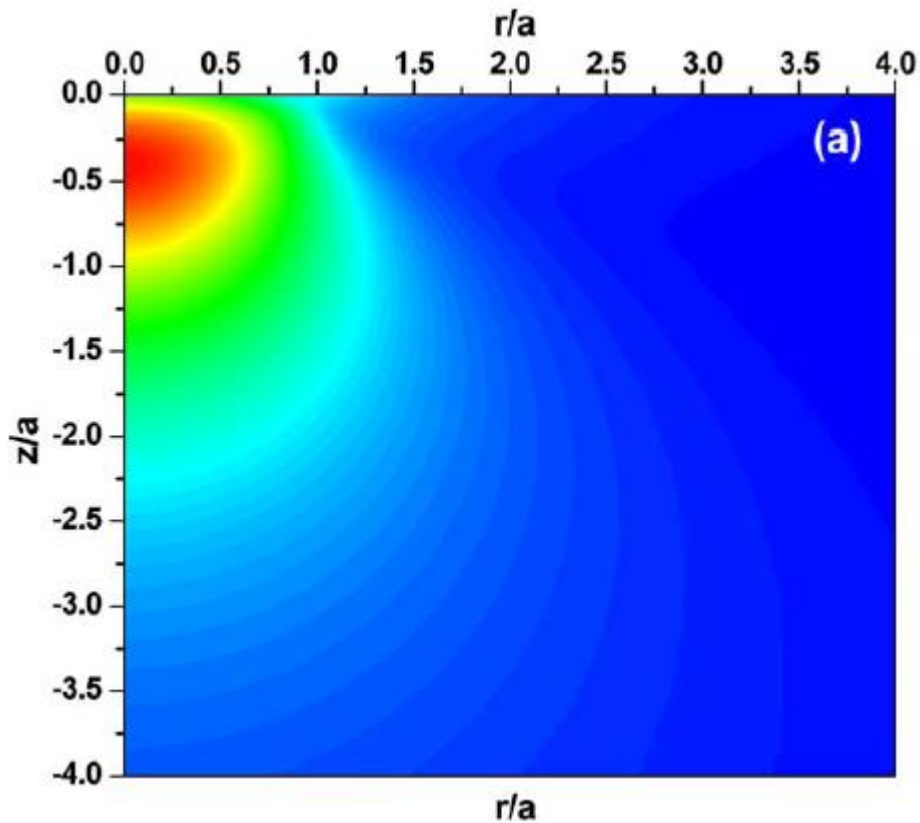
$$E_r = \left(\frac{(1 - \nu_t^2)}{E_t} + \frac{(1 - \nu_s^2)}{E_s} \right)^{-1}$$

$$A = 22.8h_c^2 + 1352h_c$$

$$R \sim 600 \text{ nm}$$

$$P = 0.5 \text{ mN}$$

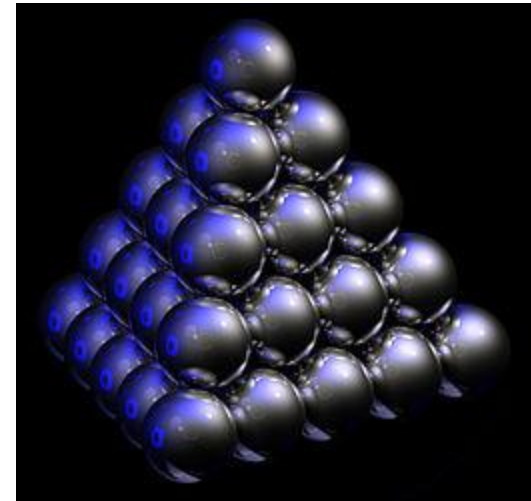
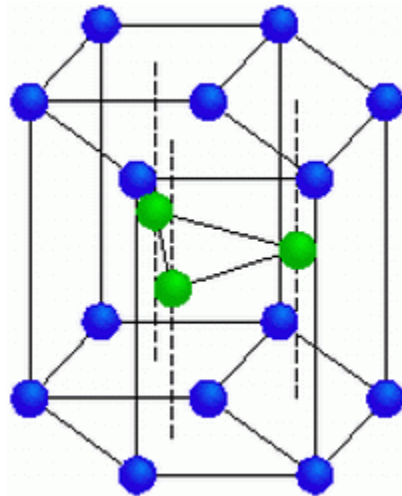
CRSS



$$\sigma_{\text{as-grown}} = P/A = 14.4 \text{ GPa}$$

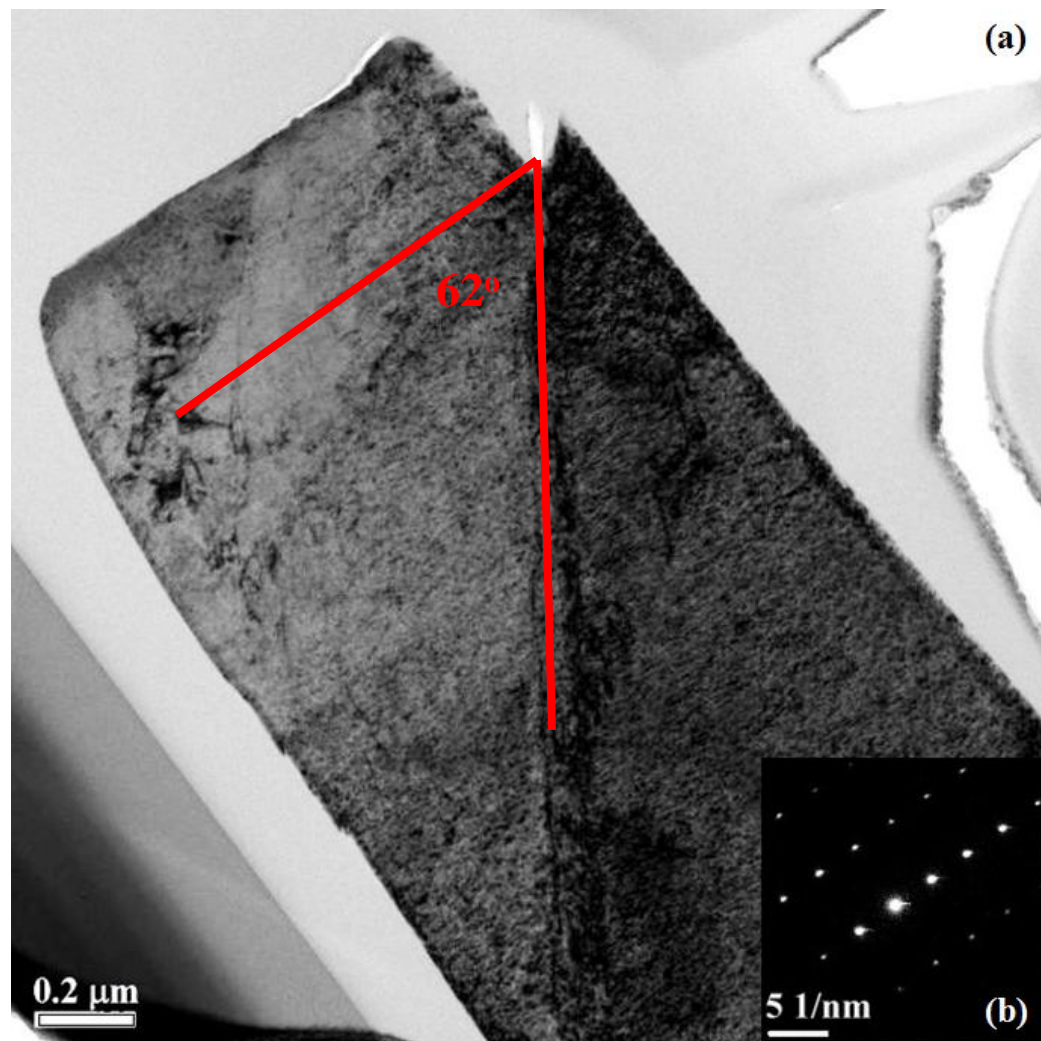
$$\sigma_{\text{annealed}} = 14.5 \text{ GPa}$$

Slip systems



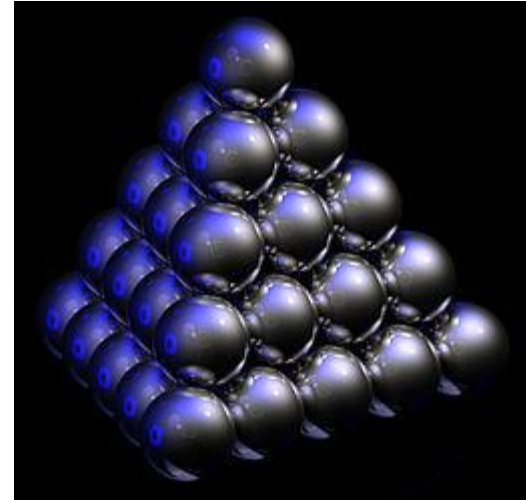
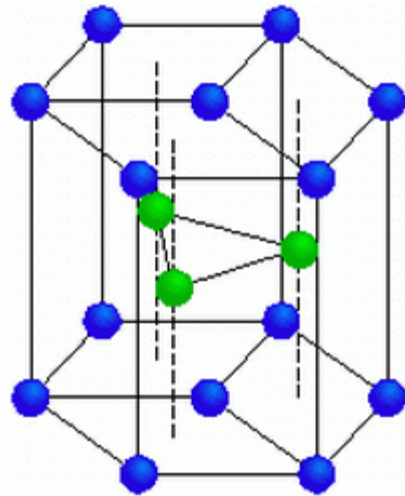
(hkil)	d	angle	[uvtw]	angle	Schmid Factor
(10-11)	1.04	62	[-1011]	47	0.34
(10-12)	0.99	43	[-2113]	31	0.38
(2-1-11)	0.924	72	[-2113]	31	0.16
(2-1-12)	0.885	58	[-2112]	17	0.16

XTEM



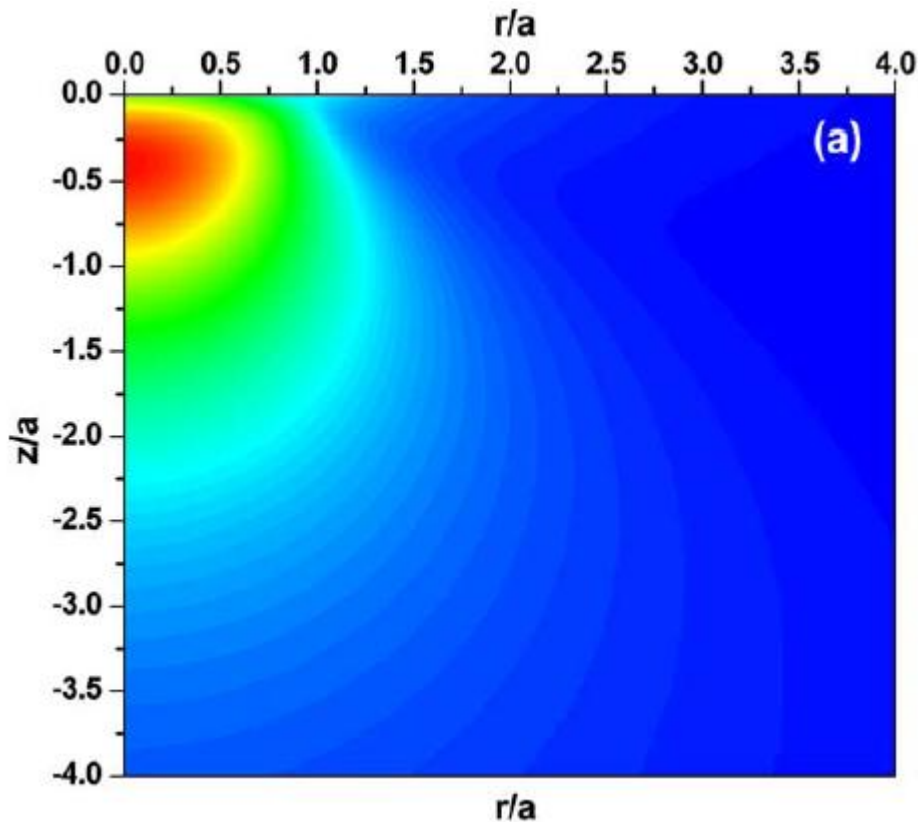
Zone axis = $[10\bar{1}0]$

Slip systems



(hkil)	d	angle	[uvtw]	angle	Schmid Factor
(10-11)	1.04	62	[-1011]	47	0.34
(10-12)	0.99	43	[-2113]	31	0.38
(2-1-11)	0.924	72	[-2113]	31	0.16
(2-1-12)	0.885	58	[-2112]	17	0.16

Maximum load



$$\sigma_{\text{as-grown}} = P/A = 14.4 \text{ GPa}$$

$$\sigma_{\text{annealed}} = 14.5 \text{ GPa}$$

$$\tau_{\text{max, CRSS}} = 14.4 \times 0.34 = 4.9 \text{ GPa}$$

at $\sim 1/2$ contact radius

$$P_{\text{max}} = \left(6PE_r^2 / \pi^3 R^2 \right)^{1/3}$$

$$P_{\text{max}} = 16 \text{ GPa}$$

$$\tau_{\text{max, CRSS}} \sim 0.3 P_{\text{max}}$$

Conclusion

- The shear stress at the very first pop-in during nanoindentation of as-grown ZnO wafer occurs at about 4.9 GPa, which is about $\mu/10$, where μ (~ 40 GPa) is the shear modulus of ZnO.
- For the annealed sample, the resolved shear stress (~ 4.9 GPa) at the first pop-in is essentially the same. This is expected since the theoretical shear strength is an intrinsic property.

Conclusion

- The corrected moduli of the as-grown and annealed micropillars are computed to be 123 ± 17 and 120 ± 15 GPa, respectively.
- The σ_{ys} and τ_p of annealed pillar is 2.7 GPa and 1 GPa, respectively.
- The σ_{ys} and τ_p of annealed pillar decrease to 1.7 GPa and 0.6 GPa, respectively.

Thank you for your attention!